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# Radiation Tolerance and Annealing Capabilities of 2MeV Proton-irradiated, Ultra-thin InP Solar Cells

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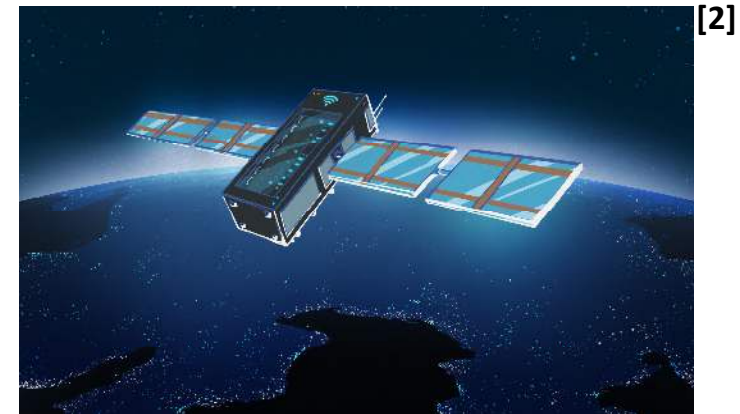
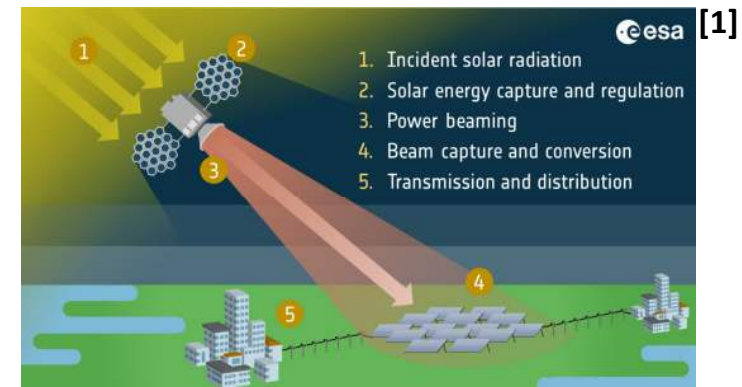
Space Photovoltaics Group

April 23, 2026

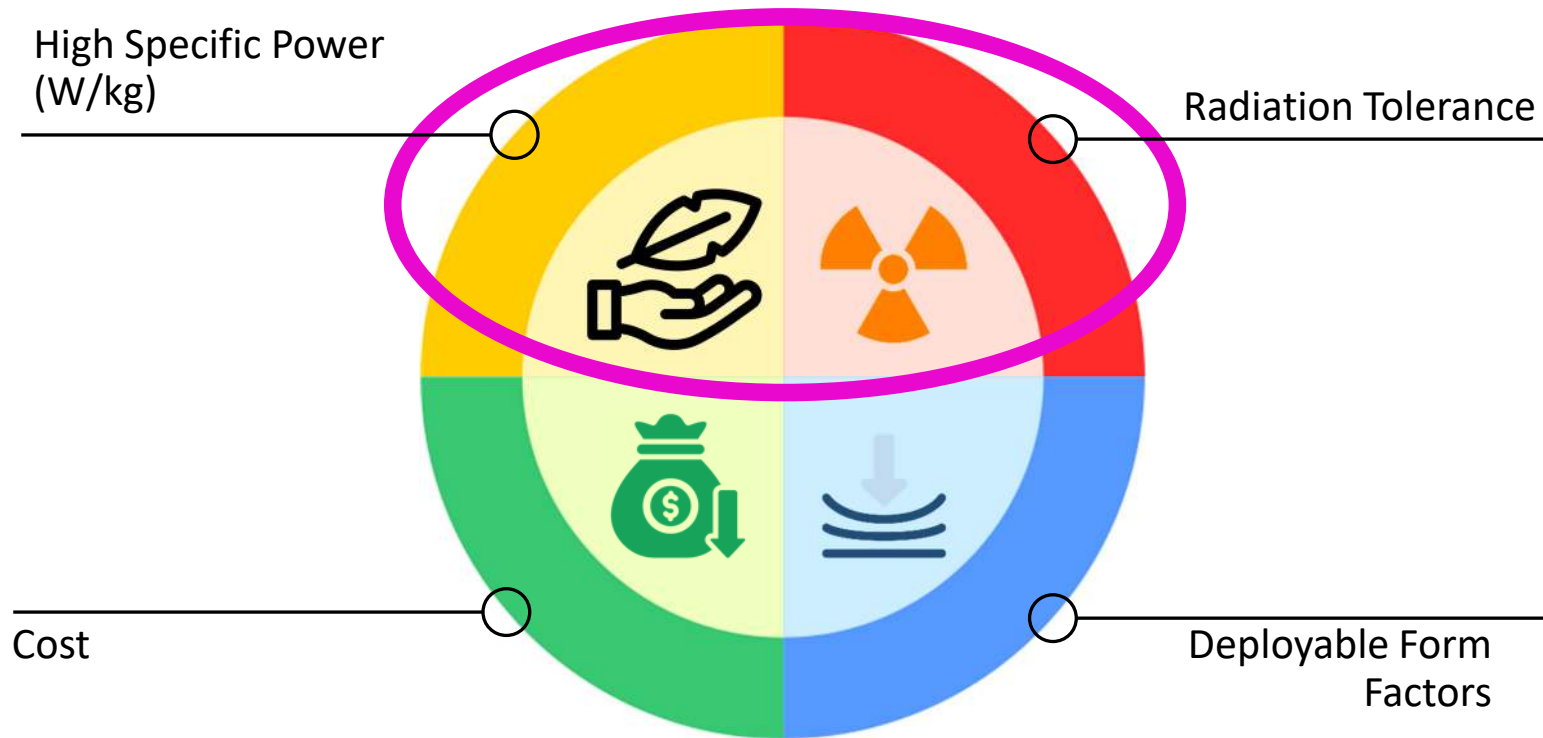
# Motivation: Enabling Resilient, Novel Space Architecture



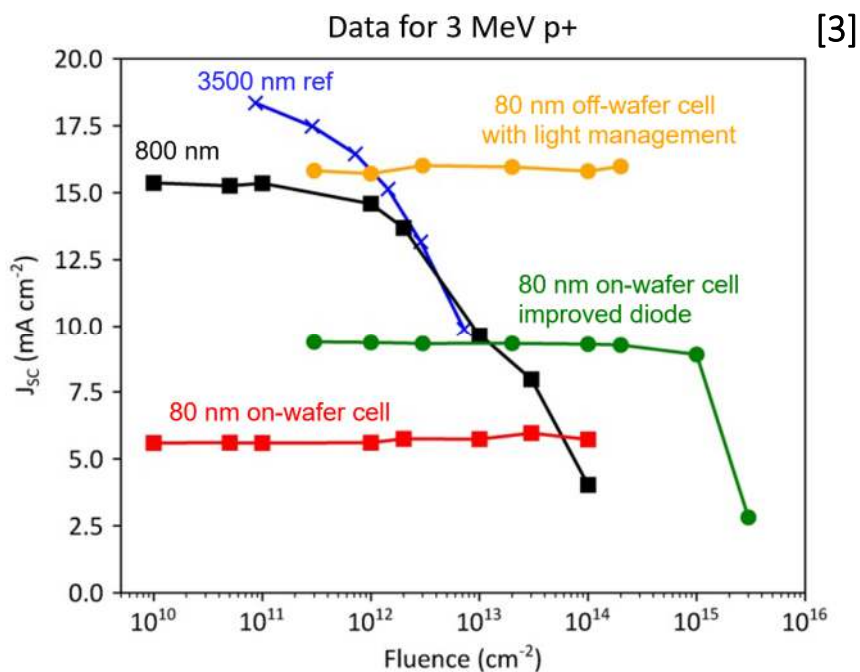
- **Current Major Players in Photovoltaics for Space Applications:**
  - Silicon: Low Cost
  - III-V Multijunction: High Performance, High Cost
- **Novel Space Architecture and Mission Profiles Require Continual Advancements in Reliable, Resilient Power Generation**
  - longer operational lifetimes
  - establishing cislunar and lunar architecture
  - space based solar power
  - orbital data centers



# Motivation: Enabling Resilient, Novel Space Architecture



# Background: Radiation Tolerance of Ultra-thin Solar Cells



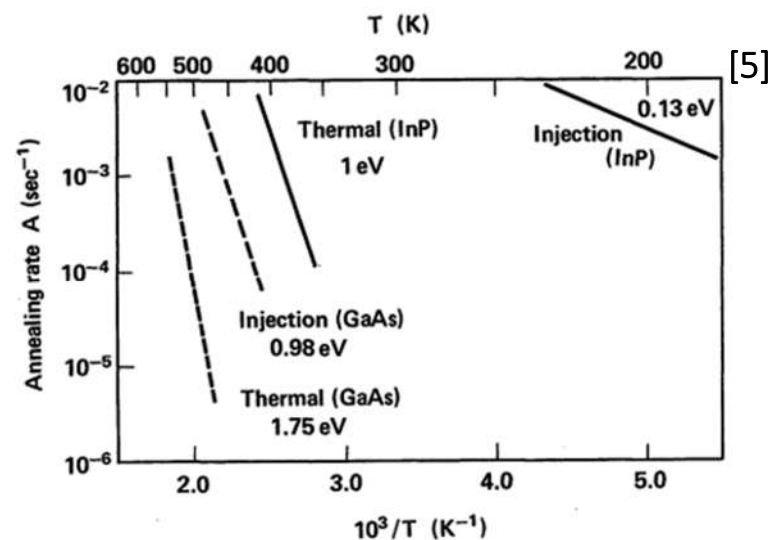
- **Radiation Induced Defects Reduce Minority Carrier Lifetime**
- **Ultra-thin Devices Reduce Carrier Collection Distance**
  - can tolerate greater reductions in minority carrier lifetime
- **Challenges Associated With Thin Absorber:**
  - absorption
  - increased surface recombination



# Background: Indium Phosphide Solar Cells

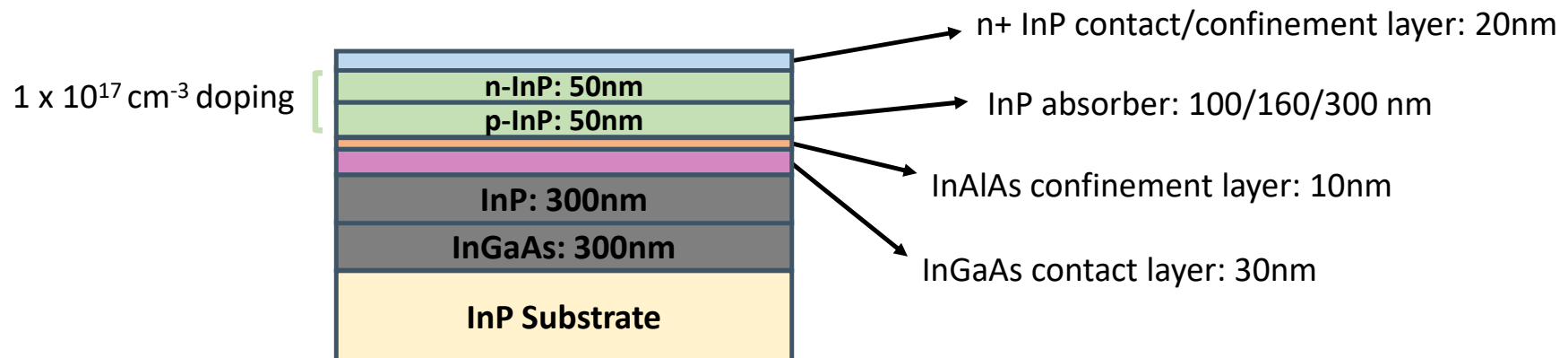


- **Non-ionizing Energy Loss (NIEL) Values for InP are the Lowest Amongst Space Solar Cell Materials [4]**
  - $\sim 10^{-2}$  MeV cm<sup>2</sup>/g for 3 MeV protons
- **Indium Phosphide Displays Thermal Annealing and Minority-carrier Injection Annealing**
- **Device Structure, Fabrication, and Radiation Particle Impact Annealing Capabilities**
  - diffused junction vs. epitaxy
  - electron vs. proton



1. Can we harness **Indium Phosphide** within an **ultra-thin** geometry to increase its absorber thickness relative to GaAs while maintaining **radiation resilience**?
2. Does **ultra-thin Indium Phosphide** exhibit minority-carrier injection and thermal annealing?

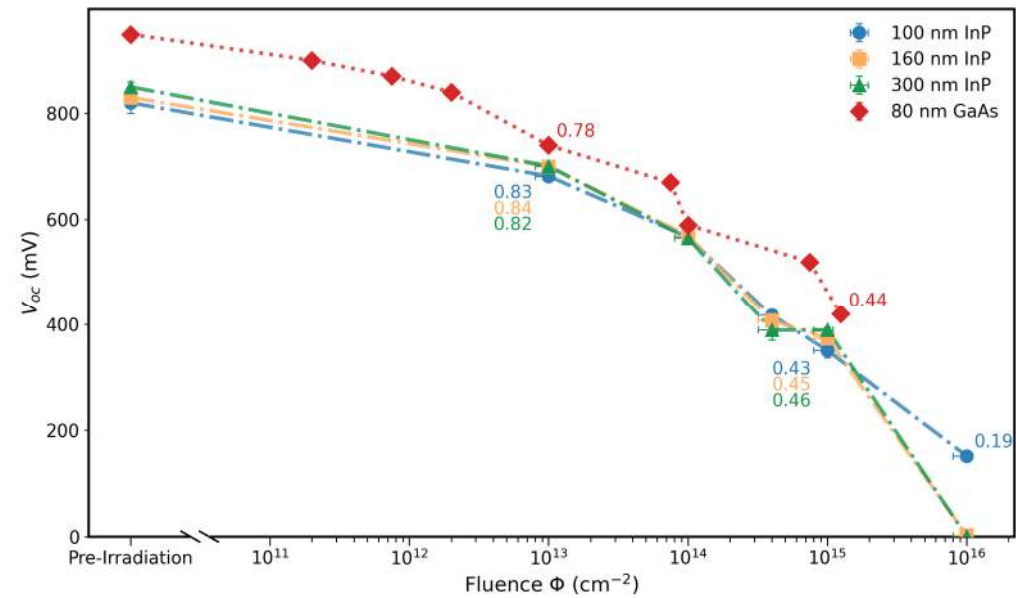
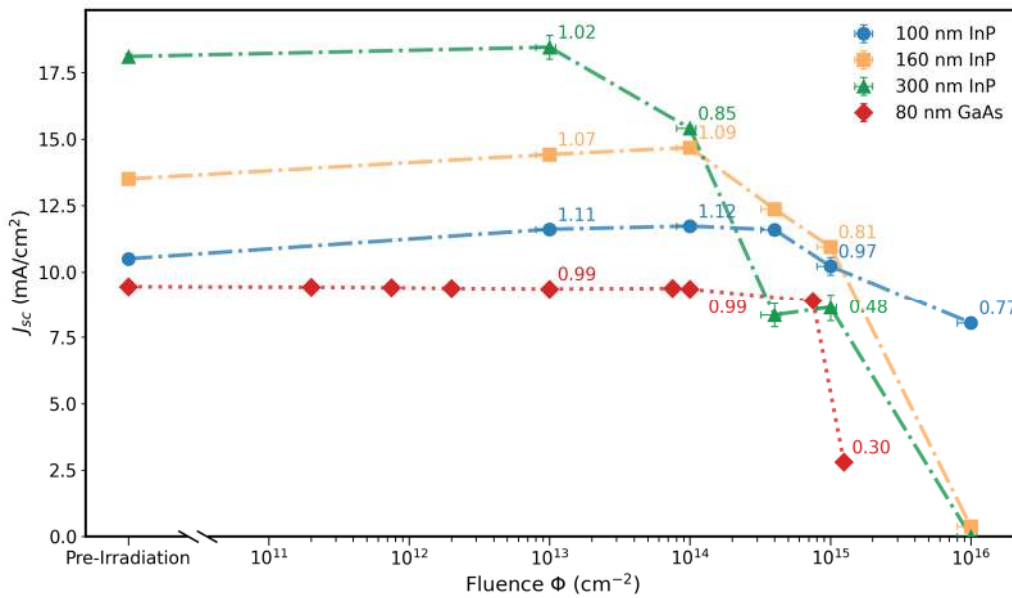
## Epitaxially Grown Ultra-thin InP (via MOCVD)



Cell Growth Completed by IQE

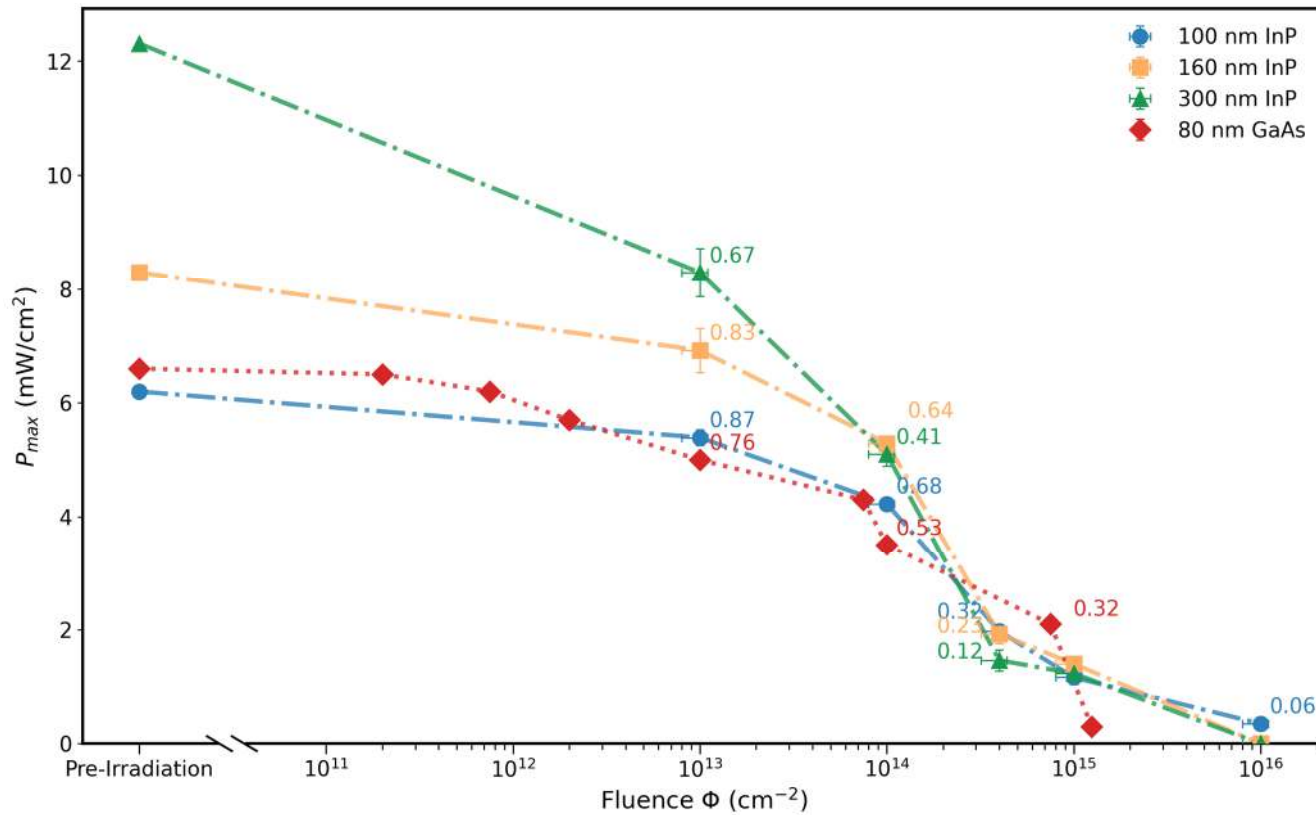
2MeV Proton Irradiation at EPSRC UK National Ion Beam Centre

# Device Parameters Across Fluence: LIV



Labels on markers indicate remaining factor

# Device Parameters Across Fluence: LIV



## Putting Fluences into Perspective

\*Without any additional shielding

2MeV p+ Fluence (cm <sup>-2</sup> )	Equiv. Years on Orbit: GEO	Equiv. Years on Orbit: GPS
10 <sup>14</sup>	0.37	0.060
10 <sup>15</sup>	3.65	0.60
10 <sup>16</sup>	36.5	6.05

← ~1.2 Years:  
80nm GaAs

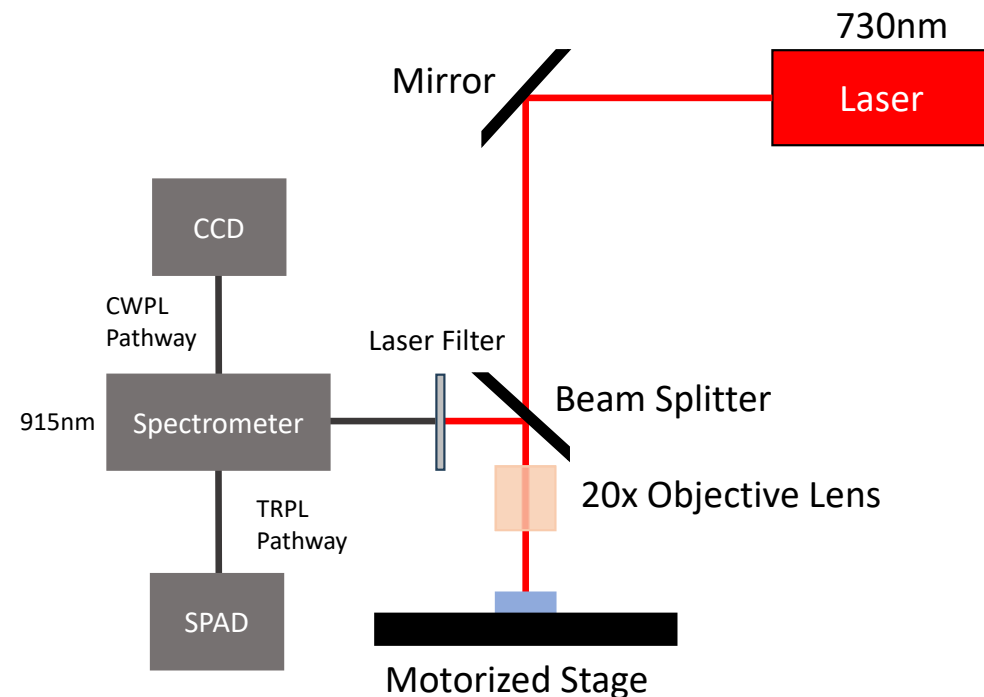
← ~6 Years:  
100nm InP

Calculated using SPENVIS

# Time-Resolved and Continuous Wave Photoluminescence



- **Characterizing Annealing Using Photoluminescence in Addition to Device Measurements**
  - **time-resolved photoluminescence (TRPL)** to measure effective carrier lifetime
  - **continuous wave photoluminescence (CWPL)** provides insight into recombination pathways, defect states, temperature effects
- **Photoluminescence Provides Non-Contact, Non-Destructive Characterization**



# Predicting Radiation-Induced Device Failure

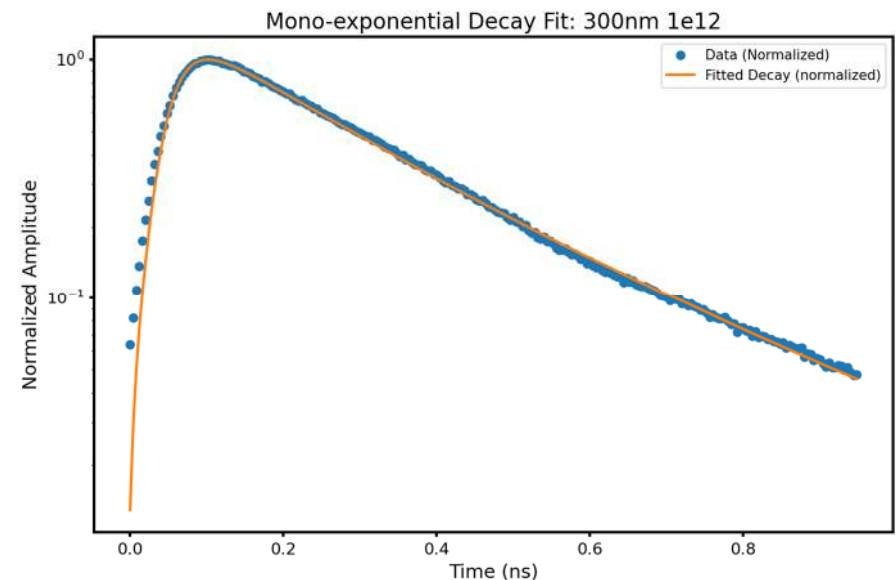


- Jsc collapse occurs when **carrier lifetime ( $\tau$ ) becomes comparable to transit time ( $t_{tr}$ )** in the device
  - solcore used to calculate electric field ( $E$ ) and drift velocity ( $v_d$ ) [6]
  - integrated across absorber width ( $W$ )

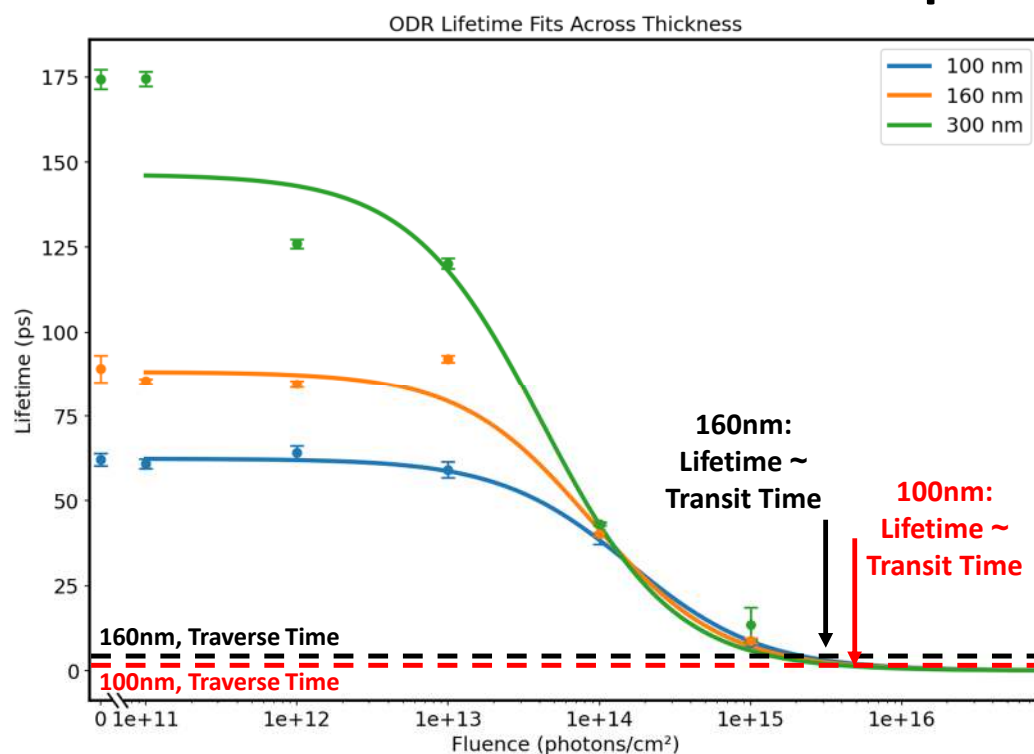
$$v_{d_{e/h}} = \frac{\mu_{e/h} E}{\left[1 + \left(\frac{\mu_{e/h} E}{v_{sat}}\right)^\beta\right]^{\frac{1}{\beta}}}$$

$$t_{tr} = \int_0^W (v_{d_{e/h}})^{-1} dx$$

## Instrument Response Function (IRF) Convolved Mono-exponential Decay Fit



## TRPL across 64 positions on each sample

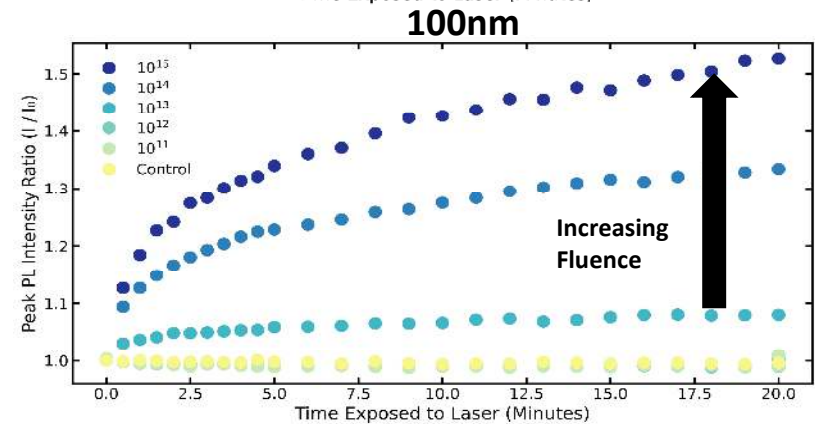
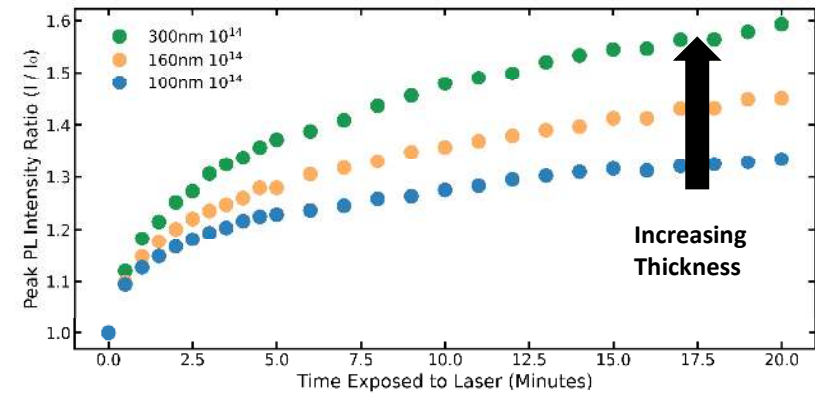
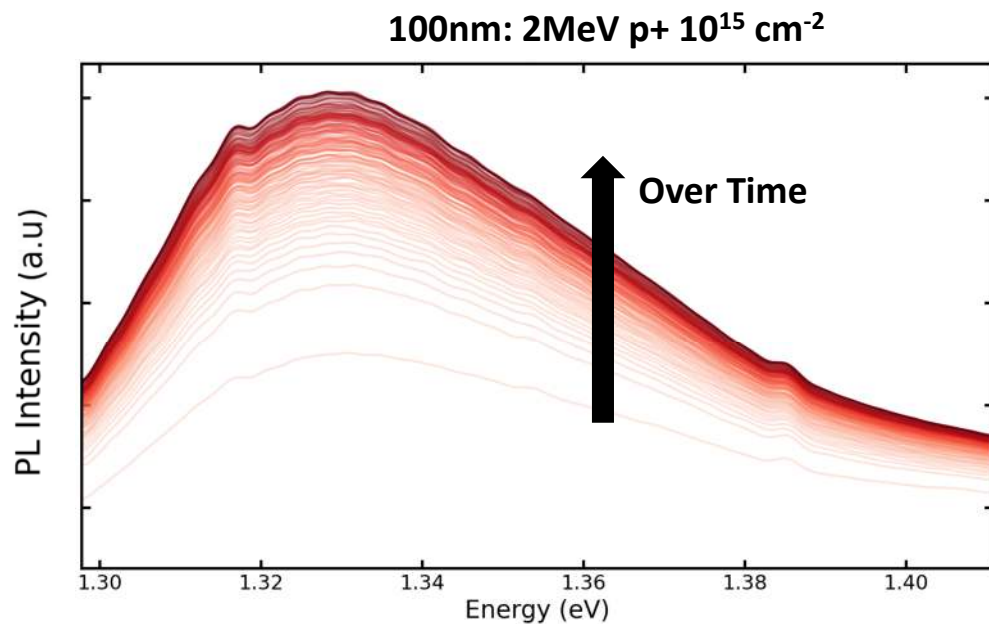


$$\frac{1}{\tau} = \frac{1}{\tau_0} + K_{\tau}\phi$$

Absorber Thickness (nm)	Lifetime Damage Constant ( $cm^2s^{-1}$ ) $K_{\tau}$	Pre-irradiation Lifetimes (ps) $\tau_0$
300	$1.64 \times 10^{-4} \pm 2.99 \times 10^{-5}$	$146.37 \pm 10.1$
160	$1.30 \times 10^{-4} \pm 1.32 \times 10^{-5}$	$86.64 \pm 2.32$
100	$9.97 \times 10^{-5} \pm 9.53 \times 10^{-6}$	$62.354 \pm 0.797$

$$80nm \text{ GaAs } K_{\tau}: 8.3 \times 10^{-4} \pm 9 \times 10^{-5}$$

# Annealing: Laser-Induced Minority-Carrier Injection

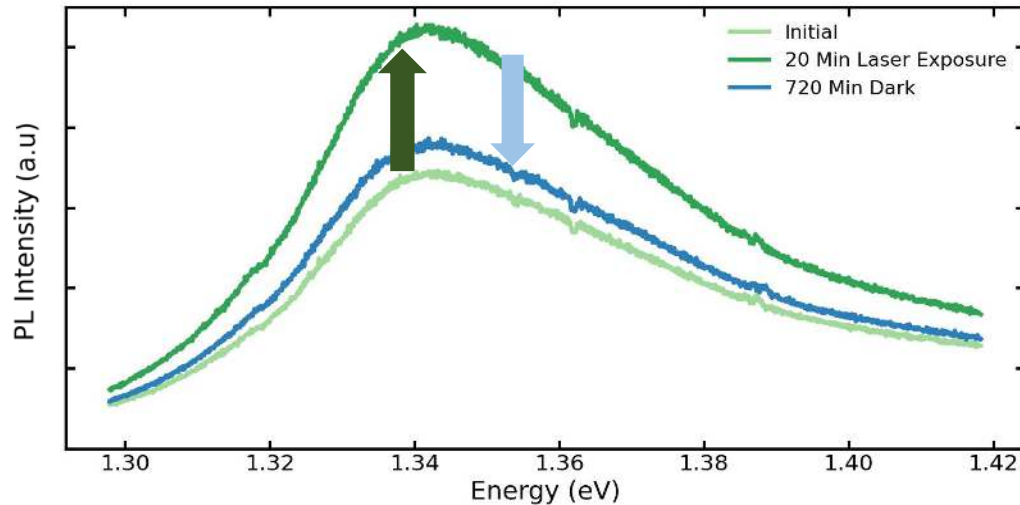


# Annealing: Laser-Induced Minority-Carrier Injection

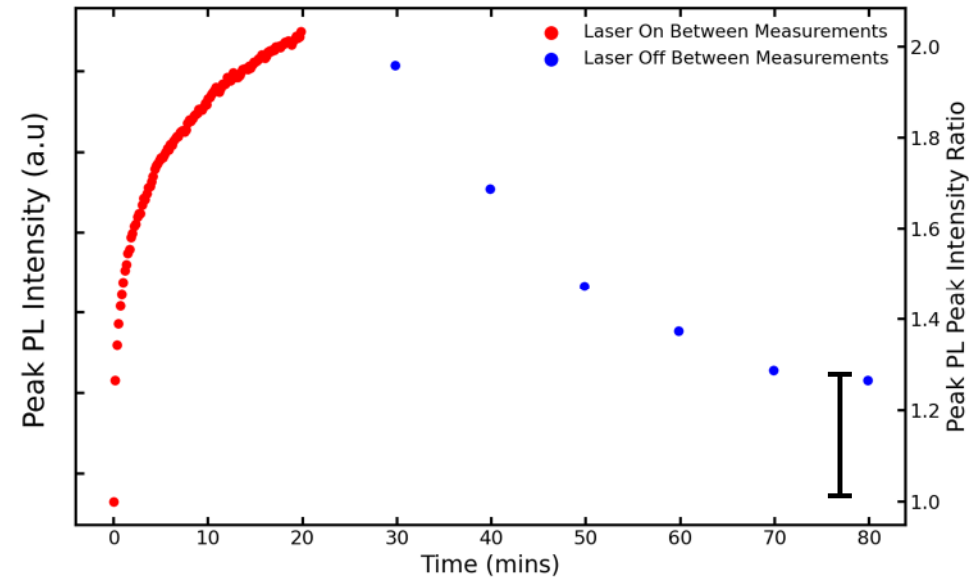


## Semi-permanent Nature

300nm: 2MeV p+ 10<sup>15</sup> cm<sup>-2</sup>



100nm: 2MeV p+ 10<sup>15</sup> cm<sup>-2</sup>

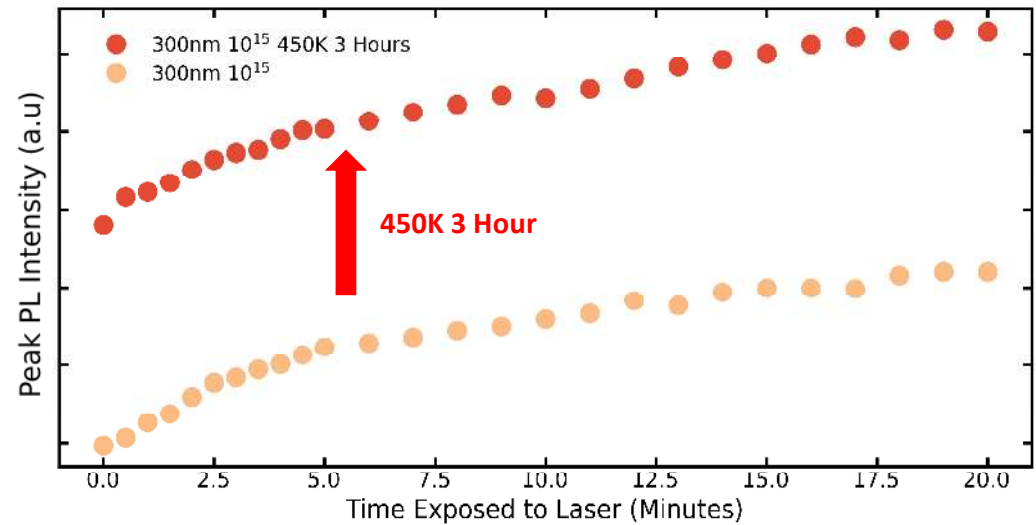
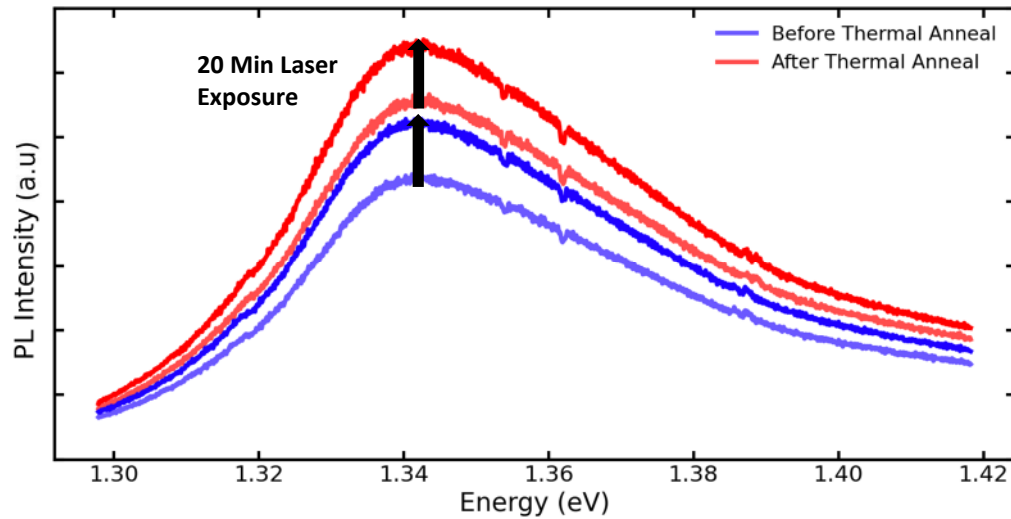


# Annealing: Thermal Annealing



## 450K 3 Hour Anneal + 20 Min Laser Exposure

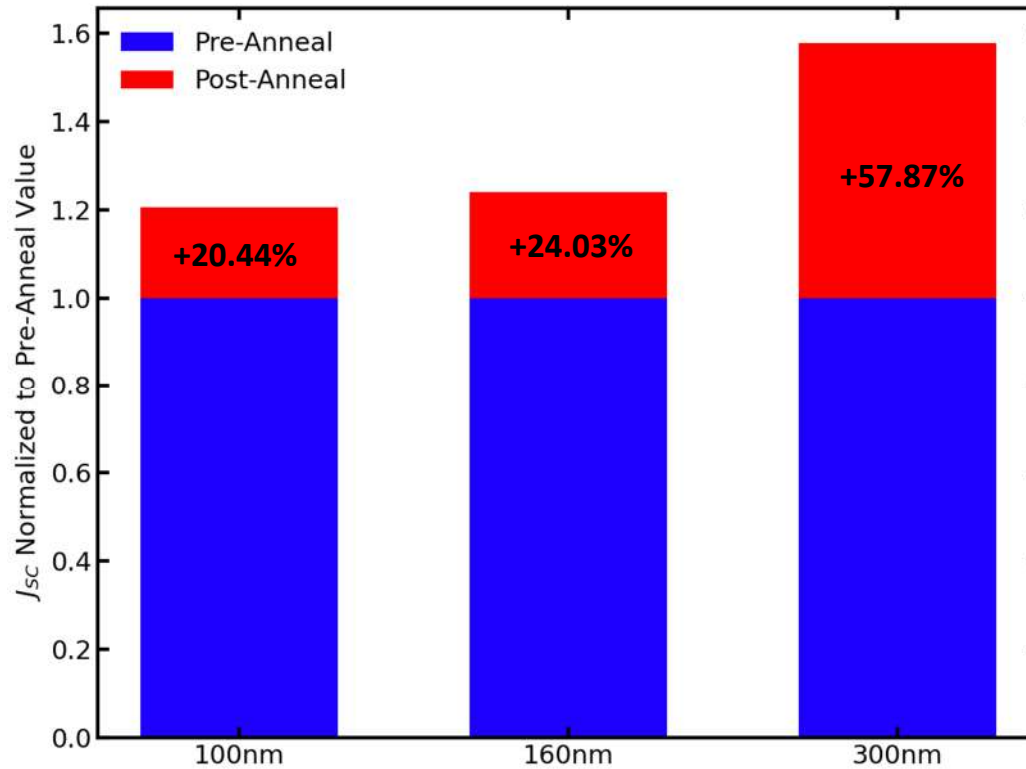
300nm: 2MeV p+  $10^{15}$  cm<sup>-2</sup>



# Annealing: Thermal Annealing – Preliminary Device Results

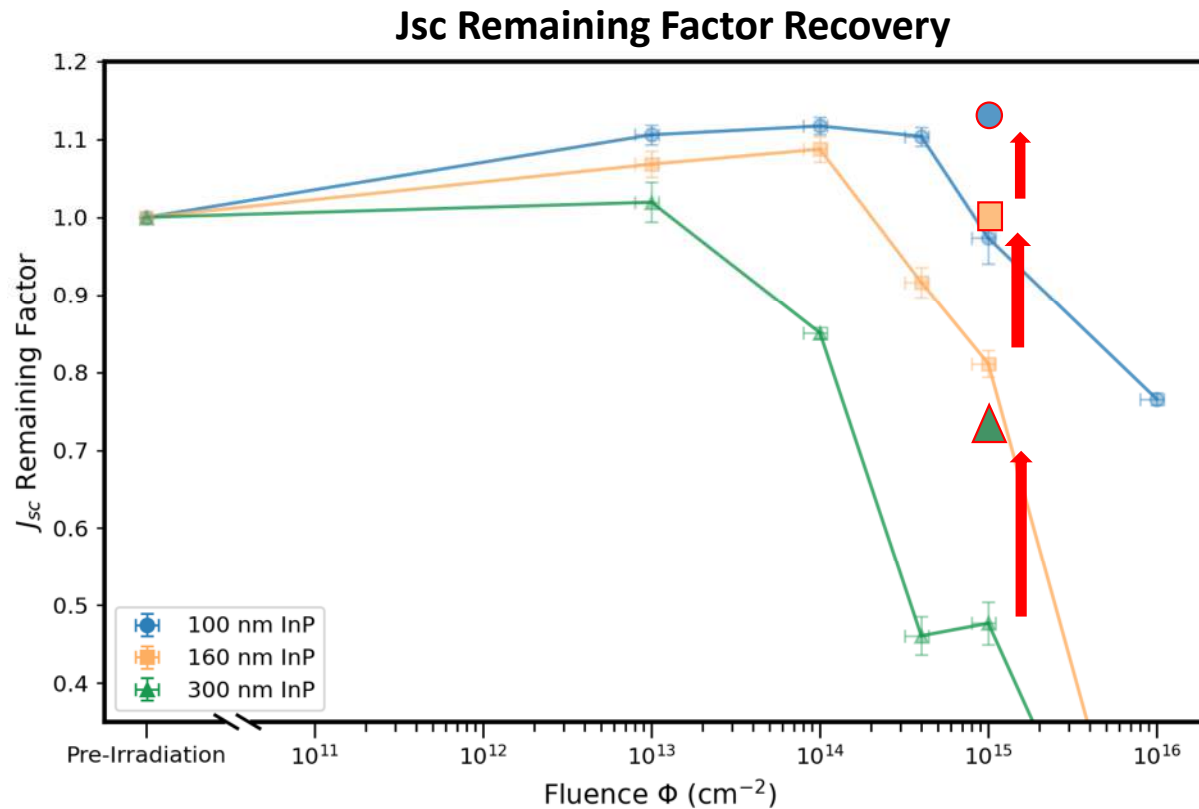


Devices Pre-Anneal  
Exposed to  $10^{15}$   
Fluence



**450K 3 Hour  
Anneal**

# Annealing: Thermal Annealing – Preliminary Device Results



**450K 3 Hour  
Anneal**

- **Ultra-thin Indium Phosphide Demonstrates Elevated Jsc RF Across Fluence**
  - 100nm InP outperforms 80nm GaAs in this metric across all tested fluences
- **Ultra-thin Indium Phosphide Exhibits Thermal and Minority-carrier injection Annealing**
  - semi-permanent minority-carrier injection annealing under high power laser illumination
  - thermal annealing improves PL intensity and device performance
- **Future Work:**
  - harnessing deep level transient spectroscopy to characterize defect states during annealing
  - additional characterization of how measured PL improvements propagate to device performance
  - incorporate light management systems

## Ultra-thin InP Presents a Promising Avenue for Radiation Resilient Power Generation in Space Applications

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